## **Electronic Supplementary Information**

# Biphenyl end-capped bithiazole co-oligomers for high performance organic thin film field effect transistors

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## **General Information**

The commercially available compounds and solvent were used as received. <sup>1</sup>H NMR and <sup>13</sup>C NMR spectra were recorded on JEOL JNM AL 400 (400 MHz) spectrometers. <sup>1</sup>H NMR spectra are reported as follows: chemical shift in ppm  $\delta$  relative to the chemical shift of CDCl<sub>3</sub> at 7.26 ppm, integration, multiplicities (s = singlet, d = doublet, t = triplet, q = quartet, m = multiplet, and br = broadened), and coupling constants (Hz). <sup>13</sup>C NMR spectra were recorded on JEOL JNM AL 400 (100.5 MHz) spectrometers with complete proton decoupling, and chemical shift reported in ppm  $\delta$  relative to the central line of triplet for CDCl<sub>3</sub> at 77 ppm. Scanning electron microscope (SEM) observation was carried out using a JEOL JSM-6500F instrument operated at an accelerating voltage of 30 kV. UV/Vis absorption spectra were recorded on a JASCO V-650DS spectrometer. Fluorescence spectra were recorded on a HITACHI F-7000 spectrophotometer and absolute fluorescence quantum yields were measured by a photon-counting method using an integration sphere on a Hamamatsu Photonics C9920-02 spectrometer. Elemental analyses were measured on J-SCIENCE Lab JM-10 and YANAKO YHS-11 in Central Analytical Facility, Institute of Multidisciplinary Research for Advanced Materials, Tohoku University. DSC was measured by a RIGAKU DSC8230 using N<sub>2</sub> atmosphere at a scan rate of 10 K/min. TGA was measured by a RIGAKU TAG8120. X-ray diffractions were measured by RIGAKU Smart Lab 9SW using Cu-Ka radiation and zero dimensional mode Dte/X as high-speed detector. The ionization potential (IP) was measured using the photoelectron spectrometer surface analyser (Riken Keiki, AC-3E). Column chromatography was carried out employing silica gel 60 N (spherical, neutral, 40~100 μm, KANTO Chemical Co.). Analytical thin-layer chromatography (TLC) was performed on 0.2 mm precoated plate Kieselgel 60 F254 (Merck).

#### Synthesis of 2,2'-bithiazole

A mixture of 2-bromothiazole (32 mmol, 2.88 mL), Pd(OAc)<sub>2</sub> (10 mol%, 718 mg), *n*-Bu<sub>4</sub>NBr (16 mmol, 5.16 g), and diisopropylethylamine (32 mmol, 5.57 mL) in toluene (12 mL) was stirred for 18 h at 105 °C. The resulting mixture was poured into water and extracted by CHCl<sub>3</sub>. After concentration, the residue was purified by silica gel chromatography, giving the corresponding 2,2'-bithiazole in 90% (2.43 g) yield as a yellow solid. <sup>1</sup>H NMR (400 MHz, CDCl<sub>3</sub>):  $\delta$  7.90 (d, 2H, *J* = 2.8 Hz), 7.45 (d, 2H, *J* = 2.8 Hz); <sup>13</sup>C NMR (100 MHz, CDCl<sub>3</sub>):  $\delta$  161.54, 143.80, 120.87.

## Synthesis of 5,5'-dibromo-2,2'-bithiazole

A mixture of 2,2'-bithiazole (6 mmol, 1.01 g) and NBS (24 mmol, 4.27 g) in DMF (30 mL) was stirred for 12 h at 60 °C. The resulting mixture was poured into water and extracted by CHCl<sub>3</sub>. After concentration, the residue was purified by recrystallization using MeOH and CHCl<sub>3</sub>, giving the corresponding 5,5'-dibromo-2,2'-bithiazole in 95% (1.85 g) yield as a white solid. <sup>1</sup>H NMR (400 MHz, CDCl<sub>3</sub>):  $\delta$  7.75 (s, 2H); <sup>13</sup>C NMR (100 MHz, CDCl<sub>3</sub>):  $\delta$  161.79, 145.06, 111.95.

## Synthesis of 5,5'-di([1,1'-biphenyl]-4-yl)-2,2'-bithiazole [BP2Tz(in)]

A mixture of 5,5'-dibromo-2,2'-bithiazole (2.5 mmol, 815 mg), [1,1'-biphenyl]-4-ylboronic acid (6.25 mmol, 1.24 g), K<sub>3</sub>PO<sub>4</sub> • nH<sub>2</sub>O (2.8 g), Pd<sub>2</sub>(dba)<sub>3</sub> • CHCl<sub>3</sub> (5 mol%, 129 mg), and X-phos (20 mol%, 238 mg) in DMF (18 mL) was stirred at 120 °C for 18 h. The mixture was filtered and the resulting residue was washed by water, MeOH, and CHCl<sub>3</sub>.

After sublimation at 330 °C under high vacuum, **BP2Tz(in)** was obtained as a yellow solid in 40% (470 mg) yield. Anal. calcd for C30H20N2S2: C 76.24, H 4.27, N 5.93, S 13.57; found: C 75.97, H 4.34, N 5.70, S 13.15%.

## Synthesis of 2-([1,1'-biphenyl]-4-yl)thiazole

[1,1'-biphenyl]-4-ylboronic acid (12.2 mmol, 2.42 g), K<sub>3</sub>PO<sub>4</sub> • nH<sub>2</sub>O (6 g), and Pd(PPh<sub>3</sub>)<sub>4</sub> were dissolved in DMF (20 mL) under nitrogen atmosphere. Then 2-bromothiazole (10.0 mmol, 0.902 mL) was added. The mixture was stirred for overnight at 100 °C. The resulting mixture was poured into water and extracted by CHCl<sub>3</sub>. After concentration, the residue was purified by silica gel chromatography, giving the corresponding 2-biphenylthiazole in 70% (1.66 g) yield as a white solid. <sup>1</sup>H NMR (400 MHz, CDCl<sub>3</sub>):  $\delta$  8.06 (d, 2H. *J* = 8.0 Hz), 7.90 (d, 1H, *J* = 2.8 Hz), 7.69 (d, 2H, *J* = 8.0 Hz), 7.64 (d, 2H, *J* = 8.0 Hz), 7.40 (t, 2H, *J* = 8.0 Hz), 7.38 (t, 1H, *J* = 8.0 Hz), 7.36 (d, 1H, *J* = 2.8 Hz); <sup>13</sup>C NMR (100 MHz, CDCl<sub>3</sub>):  $\delta$  167.99, 143.60, 142.71, 140.11, 132.39, 128.82, 127.71, 127.55, 126.96, 118.72.

#### Synthesis of 2,2'-di([1,1'-biphenyl]-4-yl)-5,5'-bithiazole [BP2Tz(out)]

To a solution of 2-([1,1'-biphenyl]-4-yl)thiazole (2.1 mmol, 577 mg) in anhydrous THF (6 mL) was added bis(2,2,6,6-tetramethylpiperidine) zinc lithium magnesium chloride complex (3.3 mL of a 0.35 M solution in THF) dropwise over 30 min at rt. The reaction mixture was stirred at room temperature for 1 h and then cooled to -40 °C. Chloranil (2.51 mmol, 616 mg) was added portion-wise over 30 min. The reaction mixture was slowly warmed to 0 °C. The mixture was quenched with sat. NH<sub>4</sub>Cl solution (3 mL) and filtered. The resulting residue was washed by water, MeOH, and CHCl<sub>3</sub>. After sublimation at 325 °C, **BP2Tz(out)** was obtained as a yellow solid in 72% (340 mg) yield. Anal. calcd for C30H20N2S2: C 76.24, H 4.27, N 5.93, S 13.57; found: C 76.24, H 4.36, N 5.92, S 13.29%

Thermal analysis



**Fig. S1** (a) DSC analysis: melting points: **BP2Tz(in)**: 336 °C; **BP2Tz(out)**: 318 °C. (b) TGA analysis: decomposition temperatures (10% loss): **BP2Tz(in)**: 447 °C; **BP2Tz(out)**: 432 °C.

#### Photoelectron yield spectroscopy



Fig. S2 PYS spectra of BP2Tz(in) and BP2Tz(out) in thin film state. IP: 5.49 eV for BP2Tz(in), 5.43 eV for BP2Tz(out).

## Theoretical calculation of HOMO and LUMO energy levels of BP2Tz series

## Computation Details<sup>[1]</sup>

Calculations of monomer molecule were performed at the DFT level by means of the hybrid B3LYP functional as implemented in Gaussian 09W. The 6-31G++(d, p) basis set was used for the all atoms.



Fig. S3 Energy diagram of theoretical calculated HOMO and LUMO energies with work function of gold and calcium.

## **Full Computational Details**

Cartesian Coordinates and Total Electron Energies

## Table S1. BP2Tz(in)

SCF Done: E(RB3LYP) = -2061.2144829

Center	Atomic	Atomic	Coord	dinates (Angstr	stroms)		
Number	Number	Туре	Х	Y	Z		
 1	6	0	-0.251714	11.764704	0.000000		
2	6	0	-1.389383	10.954582	0.000000		
3	6	0	-1.268445	9.565226	0.000000		
4	6	0	-0.008593	8.933063	0.000000		
5	6	0	1.125012	9.770753	0.000000		
6	6	0	1.007386	11.160466	0.000000		
7	6	0	0.118968	7.447142	0.000000		
8	6	0	1.375398	6.807057	0.000000		
9	6	0	1.499778	5.423604	0.000000		
10	6	0	0.367898	4.585013	0.000000		
11	6	0	-0.889459	5.216046	0.000000		

12	6	0	-1.007386	6.601681	0.000000
13	6	0	0.507777	3.127977	0.000000
14	6	0	1.663482	2.368061	0.000000
15	6	0	0.242328	0.681032	0.000000
16	16	0	-0.867503	2.041228	0.000000
17	6	0	-0.242328	-0.681032	0.000000
18	6	0	-1.663482	-2.368061	0.000000
19	6	0	-0.507777	-3.127977	0.000000
20	16	0	0.867503	-2.041228	0.000000
21	6	0	-0.367898	-4.585013	0.000000
22	6	0	0.889459	-5.216046	0.000000
23	6	0	1.007386	-6.601681	0.000000
24	6	0	-0.118968	-7.447142	0.000000
25	6	0	-1.375398	-6.807057	0.000000
26	6	0	-1.499778	-5.423604	0.000000
27	6	0	0.008593	-8.933063	0.000000
28	6	0	1.268445	-9.565226	0.000000
29	6	0	1.389383	-10.954582	0.000000
30	6	0	0.251714	-11.764704	0.000000
31	6	0	-1.007386	-11.160466	0.000000
32	6	0	-1.125012	-9.770753	0.000000
33	1	0	-0.344635	12.846564	0.000000
34	1	0	-2.378713	11.403214	0.000000
35	1	0	-2.177702	8.975698	0.000000
36	1	0	2.121631	9.345156	0.000000
37	1	0	1.905715	11.771275	0.000000
38	1	0	2.288111	7.390810	0.000000
39	1	0	2.495743	4.993580	0.000000
40	1	0	-1.796567	4.618638	0.000000
41	1	0	-2.007406	7.018669	0.000000
42	1	0	2.667288	2.774382	0.000000
43	1	0	-2.667288	-2.774382	0.000000
44	1	0	1.796567	-4.618638	0.000000
45	1	0	2.007406	-7.018669	0.000000
46	1	0	-2.288111	-7.390810	0.000000
47	1	0	-2.495743	-4.993580	0.000000
48	1	0	2.177702	-8.975698	0.000000
49	1	0	2.378713	-11.403214	0.000000

50	1	0	0.344635	-12.846564	0.000000
51	1	0	-1.905715	-11.771275	0.000000
52	1	0	-2.121631	-9.345156	0.000000
53	7	0	1.512251	1.013883	0.000000
54	7	0	-1.512251	-1.013883	0.000000

## Table S2. BP2Tz(out)

SCF Done: E(RB3LYP) = -2061.2163087

Center	Atomic	Atomic	Coordinates (Angstroms)		
Number	Number	Туре	Х	Y	Ζ
			0.226002	11 772 640	
l	6	0	-0.236002	11.772640	0.000000
2	6	0	-1.377853	10.968457	0.000000
3	6	0	-1.263874	9.578529	0.000000
4	6	0	-0.007189	8.939968	0.000000
5	6	0	1.130715	9.771878	0.000000
6	6	0	1.020064	11.162112	0.000000
7	6	0	0.113681	7.453107	0.000000
8	6	0	1.369066	6.809145	0.000000
9	6	0	1.488693	5.425535	0.000000
10	6	0	0.347246	4.603205	0.000000
11	6	0	-0.909852	5.229722	0.000000
12	6	0	-1.020064	6.615768	0.000000
13	6	0	0.505124	3.148530	0.000000
14	6	0	1.518579	1.175928	0.000000
15	6	0	0.228000	0.685073	0.000000
16	16	0	-0.878868	2.043826	0.000000
17	6	0	-0.228000	-0.685073	0.000000
18	6	0	-1.518579	-1.175928	0.000000
19	6	0	-0.505124	-3.148530	0.000000
20	16	0	0.878868	-2.043826	0.000000
21	6	0	-0.347246	-4.603205	0.000000
22	6	0	0.909852	-5.229722	0.000000
23	6	0	1.020064	-6.615768	0.000000
24	6	0	-0.113681	-7.453107	0.000000
25	6	0	-1.369066	-6.809145	0.000000

26	6	0	-1.488693	-5.425535	0.000000
27	6	0	0.007189	-8.939968	0.000000
28	6	0	1.263874	-9.578529	0.000000
29	6	0	1.377853	-10.968457	0.000000
30	6	0	0.236002	-11.772640	0.000000
31	6	0	-1.020064	-11.162112	0.000000
32	6	0	-1.130715	-9.771878	0.000000
33	1	0	-0.323444	12.854966	0.000000
34	1	0	-2.364856	11.422166	0.000000
35	1	0	-2.176242	8.993922	0.000000
36	1	0	2.125005	9.341166	0.000000
37	1	0	1.921444	11.768357	0.000000
38	1	0	2.282943	7.390920	0.000000
39	1	0	2.468372	4.960887	0.000000
40	1	0	-1.819001	4.634698	0.000000
41	1	0	-2.016739	7.040255	0.000000
42	1	0	2.406245	0.553514	0.000000
43	1	0	-2.406245	-0.553514	0.000000
44	1	0	1.819001	-4.634698	0.000000
45	1	0	2.016739	-7.040255	0.000000
46	1	0	-2.282943	-7.390920	0.000000
47	1	0	-2.468372	-4.960887	0.000000
48	1	0	2.176242	-8.993922	0.000000
49	1	0	2.364856	-11.422166	0.000000
50	1	0	0.323444	-12.854966	0.000000
51	1	0	-1.921444	-11.768357	0.000000
52	1	0	-2.125005	-9.341166	0.000000
53	7	0	-1.662023	-2.531124	0.000000
54	7	0	1.662023	2.531124	0.000000

## Thin film OFET (OTFT) device fabrication and characterization

## Fabrication OTFTs using OTS-treated SiO<sub>2</sub> substrate

A highly doped silicon wafer with a 300 nm thermally grown SiO<sub>2</sub> layer was covered with OTS. These substrates was used in the thin film deposition. Thin film transistors were fabricated by evaporating the highly pure molecules under the high vacuum (10<sup>-6</sup> Torr) with a thickness of 30 nm, as measured in situ by a quartz crystal microbalance. The thin film deposition rate maintained at 0.1 Å/sec. The top contact symmetric electrodes were deposited by evaporating gold metal through a shadow mask on the top of the thin film. The electrical characterization of thin film transistors were performed in the glove box under an inert Ar atmosphere by using a semiconductor parameter analyzer (Agilent Technology B1500A) and a CCD camera through an optical microscope.

Compound	$T_{ m sub}$ / $^{ m o} m C$	$\mu_{\rm max}$ / cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup>	$\mu_{\rm ave}$ / cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup>	$V_{ m th}$ / V	on / off
BP2Tz(in)	40	0.48	0.28	-29	10 <sup>5</sup>
	60	1.5	1.1	-31	10 <sup>6</sup>
	80	2.9	2.8	-35	10 <sup>6</sup>
	100	3.5	3.2	-28	10 <sup>8</sup>
	120	2.1	1.9	-31	10 <sup>6</sup>
	140	1.8	1.6	-19	106
	160	2.0	1.5	-27	107
	180	1.2	0.68	-26	10 <sup>5</sup>
BP2Tz(out)	40	0.085	0.075	-44	104
	60	0.17	0.13	9	10 <sup>5</sup>
	80	0.30	0.26	-5	10 <sup>5</sup>
	100	0.44	0.40	-19	10 <sup>5</sup>
	120	0.36	0.32	-15	107
	140	0.32	0.27	-1	10 <sup>5</sup>
	160	0.50	0.32	-31	10 <sup>7</sup>
	180	0.15	0.13	-54	10 <sup>5</sup>

Table S3. OTFTs performances at various substrate temperatures  $(T_{sub})$ 

## Scanning electron microscopy (SEM) image



Fig. S4 SEM image of thin film surface based on BP2Tz(in).



Figure S5. SEM image of thin film surface based on BP2Tz(out).

## Fabrication of OTFTs on TTC-SiO<sub>2</sub> substrate

BP2Tz transistors were fabricated on an n-type highly doped silicon substrate with a 300 nm-thick SiO<sub>2</sub> layer as a gate electrode and a dielectric layer. The substrates were cleaned by ultrasonication in acetone, ethanol, and 2-propanol followed by O<sub>2</sub>-plasma treatment. The substrate was subsequently modified by thermally deposited TTC with 9 nm in thickness. The BP2Tz thin film (30 nm) was deposited by a vacuum vapor deposition method. Thin film transistors were made by evaporating highly purified molecules under high vacuum (10<sup>-6</sup> Torr). The thin film deposition rate was maintained at 0.1 Å/s, and the substrate was kept at room temperature. Au was deposited onto the thin films by vacuum vapor deposition with a shadow mask. The channel length and the width were 100  $\mu$ m and 12000  $\mu$ m, respectively. The electrical characterization of thin film transistors were performed in the glove box under an inert Ar atmosphere by using a semiconductor parameter analyzer (Agilent Technology B1500A) and a CCD camera through an optical microscope.



**Fig. S6** Output (a, b) and transfer (c) characteristics of **BP2Tz(in)**-based OTFT with tetratetracontane (TTC)/SiO<sub>2</sub>/Si substrate. Carrier mobility:  $\mu_h = 0.012 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ ;  $\mu_e = 0.015 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ 



**Fig. S7** Output (a, b) and transfer (c) characteristics of **BP2Tz(out)**-based OTFT with TTC/SiO<sub>2</sub>/Si substrate. Carrier mobility:  $\mu_h = 0.01 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ ;  $\mu_e = 0.015 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ 



Fig. S8 Light emission of an ambipolar OTFT based on BP2Tz(out).

## References

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